



Vacuum Equipment - Coatings - Optics

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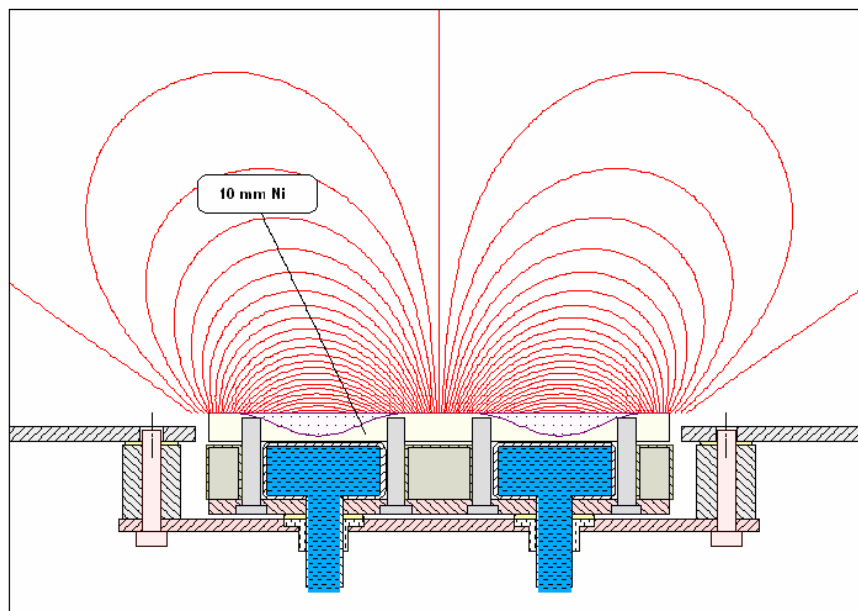
ION AND PLASMA DEVICES FOR COATINGS APPLICATIONS

Planar Magnetron Sputtering System for Magnetic Materials

This magnetron sputtering system is intended for deposition Ni and its alloys, and Cr-Ni-Cu and Cr-Ni-Ag metallizing.

Design provides either direct or indirect water cooling of massive (thickness up to 10 mm) Ni target. Powerful permanent magnets create constant values of magnetic field and accordingly high deposition rates.

Magnetron may be designed for flange and inside a vacuum chamber installation.



SPECIFICATIONS

Discharge voltage, V	450 - 550
Discharge current (for 400 mm target length), A	up to 20
Working pressure, Pa	0.08 - 0.15
Target thickness, mm	up to 10
Working gas	Ar

